

Certification of Design, Construction and Qualification

Supplier Name: Texas Instruments	Date: 11/18/2021
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Item Name	Supplier Response
1. User's Part Number:	SN74LVC1G97QDCKRQ1
2. Supplier's Part Number / Data Sheet:	SN74LVC1G97QDCKRQ1 SCES561D
3. Device Description:	CONFIGURABLE MULTIPLE-FUNCTION GATE
4. Wafer/Die Fab Location & Process ID: a. Facility name / plant #: b. Street address: c. Country:	FFAB Haggertystrasse 1, Freising Bayern, Germany 85356 Germany
5. Wafer Probe Location: a. Facility name / plant #: b. Street address: c. Country:	FFAB Haggertystrasse 1, Freising Bayern, Germany 85356 Germany
6. Assembly Location & Process ID: a. Facility name / plant #: b. Street address: c. Country:	HEFEI TONGFU MICROELECTRONICS (HFTFAT) No.578, Wei Xin Road, Economic -Technological Development, Hefei China
7. Final Quality Control A (Test) Location: a. Facility name / plant #: b. Street address: c. Country:	HEFEI TONGFU MICROELECTRONICS (HFTFAT) No.578, Wei Xin Road, Economic -Technological Development, Hefei China
8. Wafer / Die: a. Wafer size: b. Die family: c. Die mask set revision & name: d. Die photo:	200mm RLVC1G97IZ - 1G97 See attached ☐ Not available ☒
9. Wafer / Die Technology Description: a. Wafer / Die process technology: b. Die channel length: c. Die gate length: d. Die supplier process ID (Mask #) e. Number of transistors or gates f. Number of mask steps	ASL3C 0.671UM 0.671UM 1LVC1G98IZX TI Information - NDA Restrictions TI Information - NDA Restrictions
10. Die Dimensions: a. Die width: b. Die length: c. Die thickness (finished):	18.90 25.91 7.5 MILS WAFER
11. Die Metallization: a. Die metallization material(s): b. Number of layers: c. Thickness (per layer): d. % of alloys (if present):	TiW/Al Cu 2 TiW 2000 6000A Al Cu (2%) Cu 2%
12. Die Passivation: a. Number of passivation layers: b. Die passivation material(s): c. Thickness(es) and tolerances:	1 Nitride 10kA nominal
13. Die Overcoat Material (e.g. Polyimide)	
14. Die Cross-Section Photo / Drawing:	See attached ☐ Not available ☒
15. Die Prep Backside: a. Die prep method: b. Die metallization: c. Thickness(es) and tolerances:	Backgrind None 7.5 MILS WAFER

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16. Die Separation Method: a. Kerf width (μm): b. Kerf depth (if not 100% saw): c. Saw method:	N/A 100% Single ☒ Dual ☐
17. Die Attach: a. Die attach material ID: b. Die attach method: c. Die placement diagram:	ABLEBOND SID# A-03 Epoxy Dispense See attached ☐ Not available ☒
18. Package a. Type of package: b. Ball/lead count c. JEDEC designation: d. Lead (Pb) free: e. Package outline drawing:	SOT DCK 6 MO-203(AB) Yes ☒ No ☐ See attached ☐ Not available ☒
19. Mold Compound: a. Mold compound supplier and ID b. Mold compound type c. Flammability rating d. Fire retardant type / composition: e. Environmentally green f. CTE (ppm / °C) ((a)bove and (b)elow Tg)	Hitachi SID#R-27 Ion trapper version UL 94 V1 ☐ UL 94 V0 ☒ None (self extinguishing resin) Yes CTE (a): 40 CTE (b): 10
20. Wire Bond: a. Wire bond material: b. Wire bond diameter (mils): c. Type of wire bond at die: d. Type of wire bond at leadframe: e. Wire bonding diagram	Au 20.3 UM (0.8 MIL) Thermosonic Ball Bond Thermosonic Stitch Bond See attached ☐ Not available ☒
21. Leadframe: a. Paddle / flag material: b. Paddle / flag width (mils): c. Paddle / flag length (mils): d. Paddle / flag plating composition: e. Paddle/flag plating thickness (μin) f. Leadframe material: g. Leadframe bonding plating composition: h. Leadframe bonding plating thickness (μin): i. External lead plating composition: j. External lead plating thickness (μin)	Cu Alloy 28.7 36.6 None NA Cu Ag 50 – 150 micro inches (1.27 – 3.81 um) Sn 275 – 787 u-in (7 – 20 um)
22. Substrate (if applicable): a. Substrate material: b. Substrate thickness (mm): c. Number of substrate metal layers: d. Plating composition of ball solderable surface: e. Panel singulation method: f. Solder ball composition: g. Solder ball diameter (mils):	N/A N/A N/A N/A N/A N/A N/A
23. Unpackaged Die (if not packaged): a. Under Bump Metallurgy (UBM) composition: b. Thickness of UBM metal: c. Bump composition: d. Bump size:	N/A N/A N/A N/A
24. Header Material (if applicable):	

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Item Name	Supplier Response
25. Thermal Resistance a. Θ_{JA} °C/W (approx) b. Θ_{JC} °C/W (approx) c. Special thermal dissipation construction techniques	@ 0 LFM High K:239.1 Top 114.1 Bottom (Exposed Pad) NA
26. Test circuits, bias(es), and operational conditions imposed during the supplier's life and environmental tests	Not provided
27. Fault Grade Coverage (%)	Not digital circuitry
28. Maximum Process Exposure Conditions: a. MSL @ rated SnPb temperature: b. MSL @ rated Pb-free temperature: c. Maximum dwell time @ maximum process temperature	*Temperatures measured on the center of plastic package body top surface. at °C (SnPb) 1 at 260 °C (Pb-free) Per IPC/JEDEC J-STD-020D; Time within 5 °C of the specified classification temperature; Sn-Pb Eutectic Assembly-20 seconds maximum; Pb-Free Assembly 30 seconds maximum

<u>Attachments</u> Die Photo ☐ Package Outline Drawing ☐ Die Cross-Section Drawing ☐ Wire & Die Placement Diagram ☐ Test Circuits, Bias Levels, & Conditions ☐	<u>Requirements</u> 1. A separate Design, Construction & Qualification must be submitted for each P/N, wafer fab, and assembly location. 2. Design, Construction & Qualification shall be signed by the individual responsible at the supplier who can verify the above information is accurate and complete. Type name and sign below.
Completed by: Date: 11/18/2021 Name: Muhammad Amirudin Signature: Amir Title: Product Engineer	Certified by: Date: 12/30/2014 Name: Julia Streltsova Signature: CQE Title: CQE